workshop:

Etch Tech 2012: *Pushing the Limits* July 16-17, 2012

Venue: California Institute of Technology, Pasadena, CA, USA

This workshop is open to all those people working in industry and academia, with an interest in recent progress in research and development, plus future trends in the fabrication and application of micro & nano structures and devices.



Agenda Monday, July 16

Time	Talk title	Speaker
8:30-9:00	Registration & Coffee	
9:00-9:15	Welcome & Introduction to Oxford Instruments	Dan Ayres, Managing Director, Oxford Inst.
9:15-9:45	Nanoscale Applications of ALD	Zuwei Liu, LBNL/ Oxford Instruments
9:45-10:15	Advances in Deep RIE / MEMS	Michelle Bourke, Oxford Instruments
10:15-10:40	Break	
10:40-11:10	Silicon Etching for Nanomechanics	Oskar Painter, Co-Director KNI, Caltech
11:10-11:40	III V Etch for nano device applications	Bob Gunn, Oxford Instruments
11:40-12:10	OpSIS Optoelectronics Systems Integration in Silicon	Michael Hochberg, University of Delaware
12:10-1:15	Lunch	
1:15-1:45	Single Digit Nanoscale Fabrication	Deirdre Olynick, Molecular Foundry, LBNL
1:45-2:15	Fabrication of Piezoelectric Nanoelectromechanical Systems	Rassul Karabalin, Caltech
2:15-2:45	Break	
2:45-3:15	Three Dimensional Etching of Silicon Nanostructures	Sameer Walavalkar, Caltech
3:15-3:45	Fabrication of micro and nano photonic devices in monocrystalline diamond	Andrei Faraon, Caltech
3:45-4:00	Questions and close	Oskar Painter, Co-Director KNI, Caltech

Agenda Tuesday 17th July

Time	Workshop	Speaker/Facilitator
9:00 - 10:00	Plasma measurement	Leslie Lea, Principal Technologist, Oxford Inst.
10:00-11:00	Process recovery and cross contamination prevention	Craig Ward, Applications Engineer, Oxford Inst.
11:00-12:00	ALD Tutorial	Annika Peter, Technologist, Oxford Instruments
12:00-1:00	Lunch break	
1:00 - 3:00	KNI Caltech Lab Tours	

Subject to change.





